

Vacuum Systems

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Outline

- 1. Vacuum Basis
- 2. Vacuum Components
- 3. Vacuum with Beams : LHC Example

1. Vacuum Basis

Units

• The pressure is the force exerted by a molecule per unit of surface : 1 Pa = 1 N/m²

~	Pa	kg/cm ²	Torr	mbar	bar	atm
1 Pa	1	10.2 10-6	7.5 10-3	10-2	10-5	9.81 10-6
1 kg/cm ²	98.1 10 ³	1	735.5	980	0.98	0.96
1 Torr	133	1.35 10-3	1	1.33	1.33 10-3	1.31 10-3
1 mbar	101	1.02 10-3	0.75	1	10-3	0.98 10-3
1 bar	$1.01\ 10^5$	1.02	750	10^{3}	1	0.98
1 atm	101 300	1.03	760	1 013	1.01	1

As a consequence of the « vacuum force » ...

Ø (mm)	16	35	63	80	100	130	150	212
kg	2	10	32	52	81	137	182	363

Ideal Gas Law

- Statistical treatment which concerns molecules submitted to thermal agitation (no interaction between molecules, random movement, the pressure is due to molecules hitting the surface)
- For such a gas, the pressure, P [Pa], is defined by the gas density, n [molecules.m⁻³], the temperature of the gas, T [K] and the Boltzman constant k, (1.38 10⁻²³ J/K)

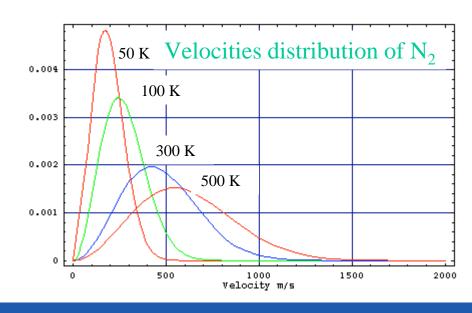
$$P = n k T$$

- The distribution of velocities, dn/dv, follows a Maxwell-Boltzmann function
- The average velocity is:

$$\overline{v} = \sqrt{\frac{8kT}{\pi m}} = 146\sqrt{\frac{T}{M}}$$

• At room temperature (m/s):

He	Air	Ar	
1800	470	400	



Total Pressure and Partial Pressure

- The gas is usually composed of several types of molecules (ex : air, residual gas in vacuum systems)
- The total pressure, P_{Tot}, is the sum of all the partial pressure, P_i (Dalton law)

$$P_{Tot} = \sum P_i = k T \sum n_i$$

Partial pressures for atmospheric air

	Gas	%	Pi (Pa)
	N_2	78.1	7.9 10 ⁴
	O_2	20.5	$2.8 ext{ } 10^3$
	Ar	0.93	$1.2 \ 10^2$
	CO_2	0.0033	4.4
	Ne	1.8 10 ⁻³	2.4 10 ⁻¹
Traces	He	5.2 10-4	7 10-2

Mean Free Path

- It is the path length that a molecules traverse between two successive impacts with other molecules. It depends of the pressure, of the temperature and of the molecular diameter.
- It increases linearly with temperature
- For air at room temperature :

$$\lambda_{air}[cm] = \frac{510^{-3}}{P[Torr]}$$

- At atmospheric pressure, $\lambda = 70 \text{ nm}$
- At 1 Torr, $\lambda = 50 \mu m$
- At 10^{-3} Torr, $\lambda = 5$ cm
- At 10^{-7} Torr, $\lambda = 500$ m
- At 10^{-10} Torr, $\lambda = 500$ km

Increasing mean free path when decreasing pressure

Turbulent and Viscous Flows

• When pumping down from atmospheric pressure, the physics is caracterised by different flow regimes. It is a function of the pressure, of the mean free path and of the components dimensions.

- Reynold number, Re :
 - if Re > 2000 the flow is turbulent
 - it is viscous if Re < 1000

$$Re = \frac{Q[Torr.l/s]}{0.089D[cm]}$$

- The turbulent flow is established around the atmospheric pressure
- In the low vacuum (10³-1 mbar), the flow is viscous. The flow is determined by the interaction between the molecules themselves. The flow is laminar. The mean free path of the molecules is small compared to the diameter of the vacuum chamber

Viscous flow: $\overline{P}D > 0.5$ [Torr.cm]

Transition and Molecular Flows

- In the medium vacuum (1-10⁻³ mbar), the flow is transitional. In every day work, this range is transited quickly when pumping down vacuum chambers. In this regime, the calculation of the conductance is complex. A simple estimation is obtained by adding laminar and molecular conductances.
- In the high vacuum (10⁻³ 10⁻⁷ mbar) and ultra-high vacuum (10⁻⁷–10⁻¹² mbar), the flow is molecular. The mean free path is much larger than the vacuum chamber diameter. The molecular interactions do not longer occurs. Molecules interact only with the vacuum chamber walls

Molecular flow: $\overline{P} D < 1.510^{-2} [Torr.cm]$

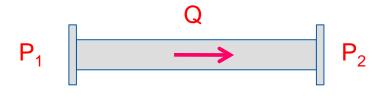
Molecular flow is the main regime of flow to be used in vacuum technology

In this regime, the vacuum vessel has been evacuated from its volume. The pressure inside the vessel is dominated by the nature of **the surface**.

Conductance

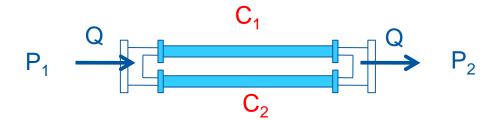
• It is defined by the ratio of the molecular flux, Q, to the pressure drop along a vacuum vessel. It is a function of the shape of the vessel, the nature of the gas and its temperature.

$$C = \frac{Q}{(P_1 - P_2)}$$



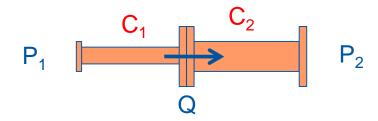
Adding conductances in parallel

$$\mathbf{C} = \mathbf{C}_1 + \mathbf{C}_2$$



Adding conductances in series

$$\frac{1}{C} = \frac{1}{C_1} + \frac{1}{C_2}$$



Conductance Calculus in Molecular Regime

•For an orifice :

$$C = \sqrt{\frac{kT}{2\pi m}}A; \quad C_{air, 20^{\circ}}[l/s] = 11.6 A[cm^2]$$

The conductance of an orifice of 10 cm diameter is 900 l/s

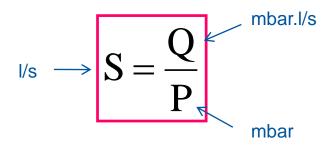
• For a tube : $C = \frac{1}{6} \sqrt{\frac{2\pi kT}{m}} \frac{D^3}{L}; \quad C_{air, 20^{\circ}}[l/s] = 12.1 \frac{D[cm]^3}{L[cm]}$

The specific conductance of a tube of 10 cm diameter is 120 l/s.m

To increase the conductance of a vacuum system, it is better to have a vacuum chamber with large diameter and short lenght

Pumping Speed

• The pumping speed, S, is the ratio of the flux of molecules pumped to the pressure



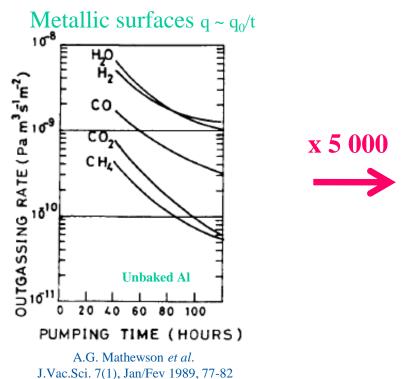
- S range from 10 to 20 000 l/s
- Q range from 10⁻¹⁴ mbar.l/s for metalic tubes to 10⁻⁵ 10⁻⁴ mbar.l/s for plastics

3 orders of magnitude for pumping vs
10 orders of magnitude for outgassing

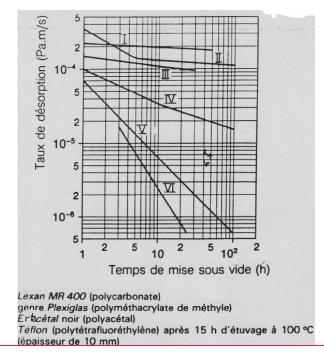
Outgassing MUST be optimised to achieve UHV

Outgassing

- •The outgassing rate, q, of a surface is the number of molecules desorbed from a surface per unit of surface and per unit of time
- It is a function of the surface nature, of its cleanliness, of its temperature and of the pump down time.
- In all vacuum systems, the final pressure is $\frac{\text{driven}}{\text{driven}}$ by the outgassing rate : $P_{\text{final}} = Q/S = qA/S$



Plastic surfaces $q \sim q_0/\sqrt{t}$



Good Vacuum Design :

Use ONLY metallic surfaces and reduce to ZERO the amount of plastics



Cleaning Methods

- Several means are used in vacuum technology to reduce the outgassing rates
- Chemical cleaning is used to remove gross contamination such as grease, oil, finger prints.
- Example of CERN LHC beam screens :

Degreasing with an alkaline detergent at 50°C in an ultrasonic bath

Running tap water rinse

Cold demineralised water rinse by immersion

Rinse with alcohol

Dry with ambient air

Vacuum firing at 950°C is used to reduce the hydrogen content

from stainless steel surface

Length: 6 m Diameter: 1 m

Maximum charge weight: 1000 Kg Ultimate pressure: 8 10-8Torr

Pressure at the end of the treatment: high 10⁻⁶ Torr



cuves for beam screens

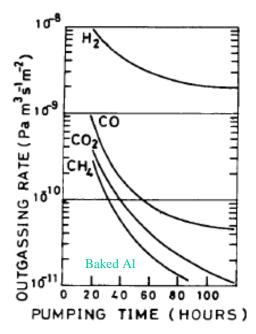


- Glow discharges cleaning is used to remove by sputtering the adsorb gases and the metal atoms
- Wear gloves to handle the material

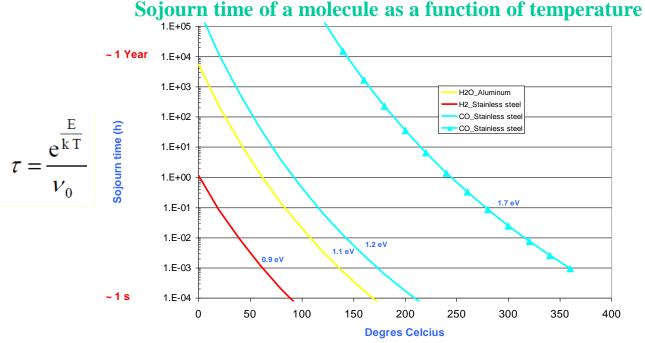


In Situ Bake Out

- The outgassing rate of unbaked surfaces is dominated by H₂0.
- A bake-out above 150 degrees increase the desorption rate of H₂O and reduce the H₂O sojourn time in such a way that H₂ become the dominant gas



A.G. Mathewson *et al.* J.Vac.Sci. 7(1), Jan/Fev 1989, 77-82



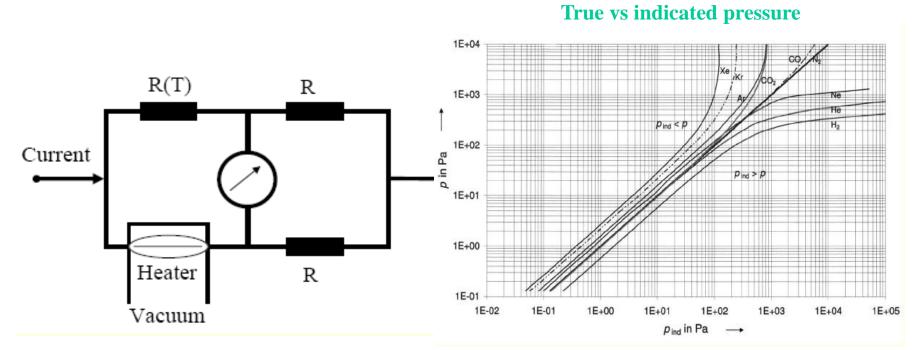
Stainless steel after 50 h of pumping (Torr.l/s/cm²)

	H2	CH4	H2O	CO	CO2
Unbaked	7 10-12	5 10-13	3 10-10	5 10-12	5 10-13
Baked	5 10 ⁻¹³	5 10 ⁻¹⁵	1 10 ⁻¹⁴	1 10 ⁻¹⁴ s and Engineering, Wo	1 10 ⁻¹⁴

2. Vacuum Components

Pirani Gauge

- Pirani gauges are commonly used in the range 1 atm -10⁻⁴ mbar.
- The operating principle is based on the variation of the thermal conductivity of the gases as a function of pressure. A resistor under vacuum is heated at a constant temperature (~ 120°C). The heating current required to keep the temperature constant is a measure of the pressure.
- In the viscous regime, the thermal conductivity is independent of the pressure. Therefore pressure readings given above 1 mbar are wrong!

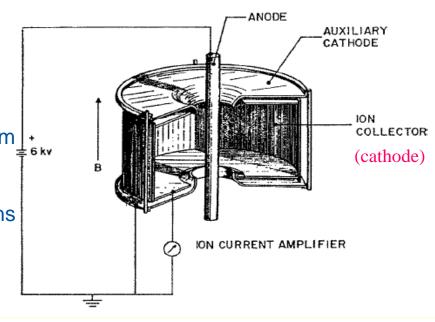






Penning Gauge

- •Penning gauges are commonly used in the range 10⁻⁵ -10⁻¹⁰ mbar. They are use for interlocking purposes
- It is a cold cathode ionisation gauge *i.e.* there are no hot filament
- The operating principle is based on the measurement of a discharge current in a Penning cell which is a function of pressure : $I^+ = P^n$, n is close to 1
- •At high pressure the discharge is unstable due to arcing.
- At low pressure, the discharge extinguishes which means zero pressure reading.
- Electrons are produced by field emission and perform oscillations due to the magnetic field
- Along the path length, molecules are ionised and ions are collected onto the cathode
- WARNING: leakage current on the HV cables simulates a higher pressure



P. Redhead. J.Vac.Sci. 21(5), Sept/Oct 2003, S1-S5

Bayard-Alpert Gauge

- •Bayard-Alpert gauges are used for vacuum measurement purposes in the range 10⁻⁵ -10⁻¹² mbar.
- It is a hot filament ionisation gauge. Electrons emitted by the filament perform oscillations inside the grid and ionise the molecules of the residual gas. Ions are then collected by an electrode.

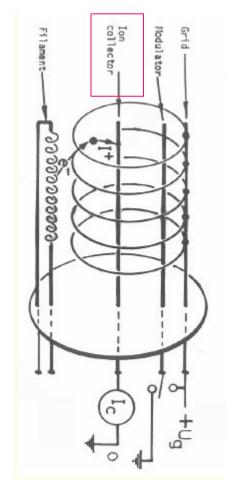
$$I^+ = I^- \sigma n L$$

Where:

I⁺ is the ion current
I⁻ is the filament current
σ is the ionisation cross section
n the gas density
L the electron path length

- The gauge needs to be calibrated
- X-ray limit of a $\sim 2 \cdot 10^{-12}$ mbar



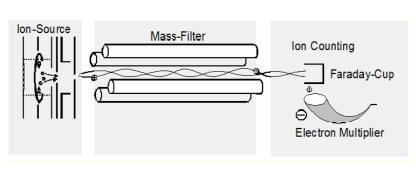


Residual Gas Analysers

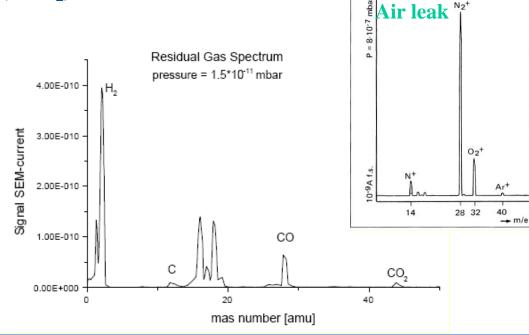
- Residual Gas Analysers are used in the range 10⁻⁴ -10⁻¹² mbar. Their purpose is to do gas analysis
- A filament produces electrons which ionise the residual gas inside a grid. A mass filter is introduced between the grid and the ion collector. The ion current can be measured in Faraday mode or in secondary electron multiplier mode.
- It is a delicate instrument which produces spectrum sometimes difficult to analyse



The RGA needs to be calibrated



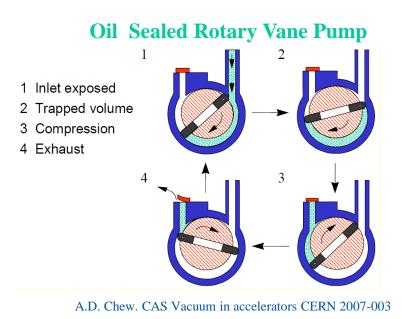
G.J. Peter, N. Müller. CAS Vacuum in accelerators CERN 2007-003

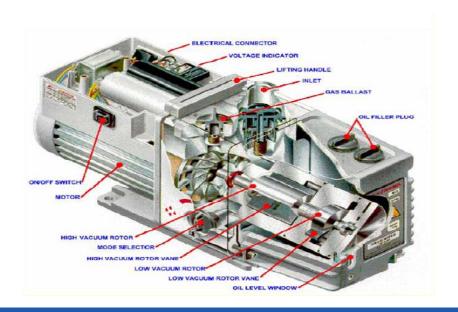




Primary Pumps

- •Are used to pump down from atmosphere down to 10⁻² mbar with a speed of a few m³/h
- They are usually used as a backing pump of turbomolecular pumps
- Two categories : dry and wet pumps.
- Dry pumps are expensive and need additional cooling (water)
- Wet pumps are operating with oil which acts as a sealing, a lubricant, a heat exchanger and protects parts from rust and corrosion



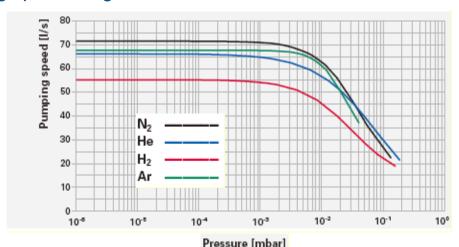


Turbomolecular Pump

• This pump operates in the molecular regime and is used to pump down an accelerator vacuum system. Usually, it is installed with its primary pump on a mobile trolley: it can be removed after valving off

• Its ultimate pressure can be very low: 10⁻¹¹ mbar

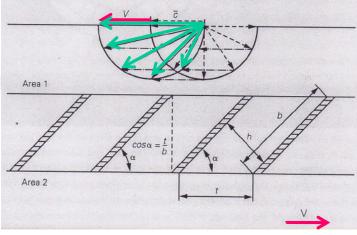
Its pumping speed range from 10 to 3 000 l/s



• The pumping mechanism is based on the transfer of impulse. When a molecule collide a blade, it is adsorbed for a certain lenght of time. After re-emission, the blade speed is added to the thermal speed of the molecules. To be significant, the blade speed must be comparable to the thermal speed hence it requires fast moving surfaces (~ 40 000 turns/min)

• The compression ratio (P_{inlet}/P_{outlet}) increase exponentially with \sqrt{M} : "clean" vacuum without hydrocarbons. So, the oil contamination from the primary pump is avoided

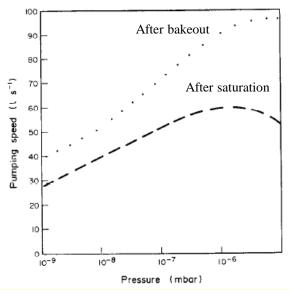


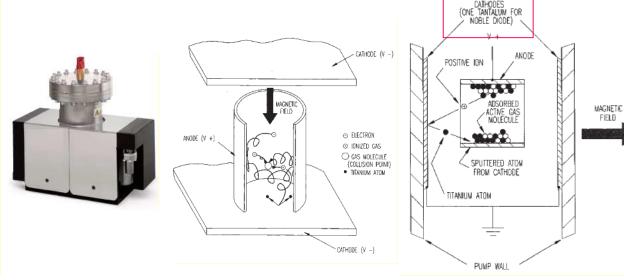


Sputter Ion Pump

- •This pump operate in the range 10⁻⁵ -10⁻¹¹ mbar. It is used to maintain the pressure in the vacuum chamber of an accelerator.
- Their pumping speed range from 1 to 500 l/s
- When electrons spiral in the Penning cell, they ionised molecules. Ions are accelerated towards the cathode (few kV) and sputter Ti. Ti, which is deposited onto the surfaces, forms a chemical bounding with molecules from the residual gas. Noble gases and hydrocarbons ,which does not react with Ti, are buried or implanted onto the cathode.

• Advantage: like for a Penning gauge, the collected current is proportional to the pressure. It is also used for interlocking.





M. Audi. Vacuum 38 (1988) 669-671

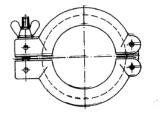


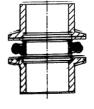
Flanges and Gaskets

- For primary vacuum, elastomer seals and clamp flanges are used
- KF type components:

Many fittings (elbows, bellows, T, cross, flanges with short pipe, reductions, blank flanges ...)

ISO diameters





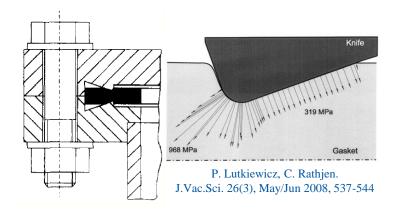


- For ultra high vacuum, metalic gaskets and bolds flanges are used
- Conflat® Type components :

Copper gaskets, blank flanges, rotable flanges, welding flanges, elbows, T, crosses, adaptators, zero length double side flanges, windows ...

ISO diameters





Tubes, Bellows, Valves

- Metallic tubes are preferred (low outgassing rate)
- Stainless steel is appreciated for mechanical reason (machining, welding)



Copper tubes

Bellows are equipped with RF fingers (impedance)





Valves are used for roughing and sectorisation

Roughing valve



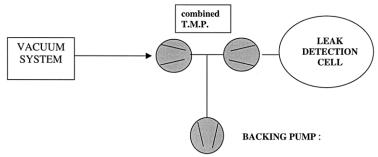


Sector valves



Leak Detection

- •The vacuum system of an accelerator must be leak tight!
- All vacuum components must follow acceptance tests (leak detection, bake out, residual gas composition and outgassing rate) before installation in the tunnel
- Virtual leaks, due to a closed volume, must be eliminated during the design phase. Diagnostic can be made with a RGA by measuring the gas composition before and after venting with argon.
- · Leaks could appear:
 - during components constructions at welds (cracks or porosity)
 due to porosity of the material
 during the assembly and the bake-out of the vacuum system (gaskets)
 during beam operation due to thermal heating or corrosion
- Detection method: He is sprayed around the test piece and a helium leak detector (*i.e.* a RGA tune to He signal) is connected to the device under test.



Counter flow method



3. Vacuum with Beams: LHC Example

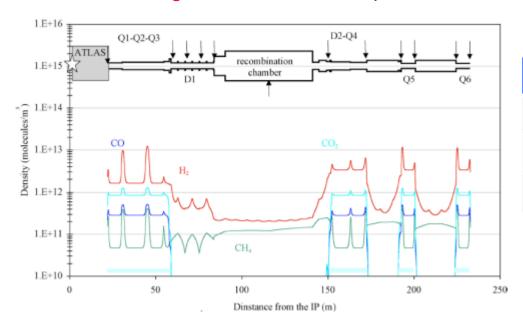
Design value: a challenge with circulating beams

- Life time limit due to nuclear scattering ~ 100 h
 - n ~ 10^{15} H₂/m³
 - <P_{arc}> < 10⁻⁸ mbar H₂ equivalent
 - ~ 80 mW/m heat load in the cold mass due to proton scattering

$$\tau = \frac{1}{\sigma \, c \, n}$$

$$P_{cold \, mass} = \frac{IE}{c \, \tau}$$

Minimise background to the LHC experiments



	H2_eq / m3	mbar
<lss<sub>1 or 5></lss<sub>	~ 5 10 ¹²	10-10
<atlas></atlas>	~ 10 ¹¹	10-11
<cms></cms>	~ 5 10 ¹²	10-10

A. Rossi, CERN LHC PR 783, 2004.

Why a Challenge?

Because, the static pressure increases by several orders of magnitude due to the dynamics effects related to the presence of a beam

(next 4 slides are just a flavor of the main phenomena which are taking place in an accelerator)

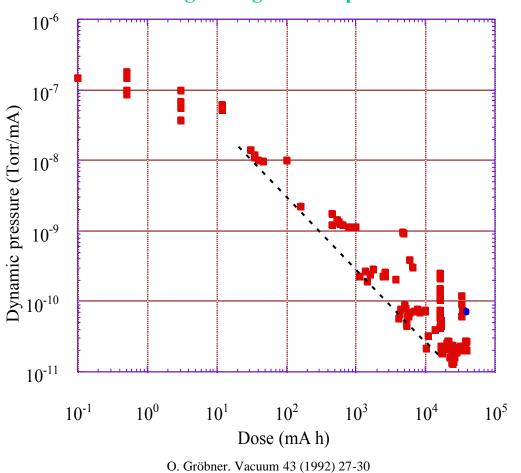
3.1 Dynamic Effects

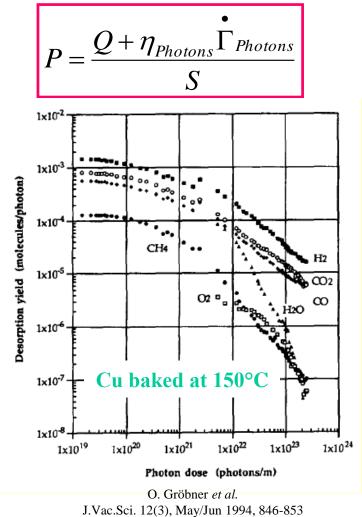
Photon Stimulated Desorption

- •Synchrotron radiation induce gas desorption : SR machine, LEP, LHC
- Heat load and gas load

• η_{photon} is the photon desorption yield







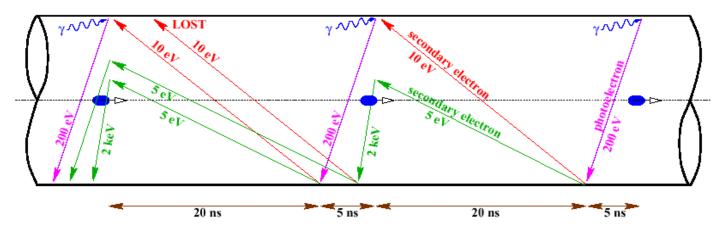
Electron Cloud: the Mechanism

- In modern machine with dense bunches and large positive current : KEK-B, PEP-II, SPS, RICH, LHC ...
- Emittance growth, gas desorption and heat load in cryogenic machine
- Key parameters :

bunch structure & current vacuum chamber dimension magnetic field secondary electron yield photon electron yield electron and photon reflectivities

$$P = rac{Q + \eta_{Electrons}}{S}$$

. . .



Schematic of electron-cloud build up in the LHC beam pipe.

F. Ruggiero et al., LHC Project Report 188 1998, EPAC 98

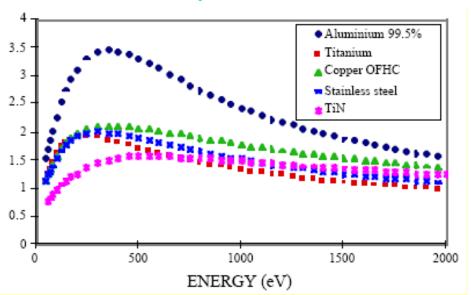


Electron Cloud: the Recipes

- •Play with the key parameters :
 - Reduce photoelectron yield (perpendicular vs grazing incidence)
 - Reduce secondary electron yields (scrubbing, TiZrV coatings, carbon coatings, geometry ..)
 - Reduce the amount of electrons in the system (solenoid magnetic field, clearing electrodes, material reflectivity ...)
 - Adapt the bunch structure or the chamber geometry to reduce multiplication

• ...

Secondary Electron Yield



N. Hilleret et al., LHC Project Report 433 2000, EPAC 00



Beam Induced Multipacting along the Beam Pipe

- Key parameters:
 - **Operational** - beam structure parameters
 - bunch current
 - vacuum chamber dimension
 - secondary electron yield (SEY)
 - photoelectron yield
 - electron and photon reflectivities

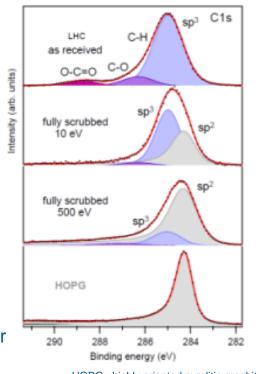
- Mitigations:
 - NEG coating with low SEY (~ 1.1)
 - Beam scrubbing to reduce SEY :

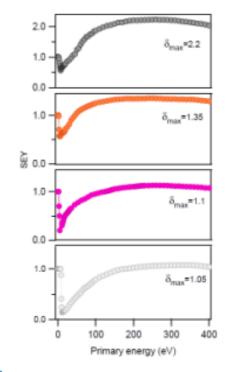
Modification of C1s core level Conversion $sp^3 => sp^2$ High energy electrons increase the number of graphitic like C-C bounds

- Monitored by ESD reduction

$$P = rac{Q + \eta_{Electrons}}{S} \overset{ullet}{\Gamma}_{Electrons}$$

R. Cimino et al. PRL 109, 064801(2012)

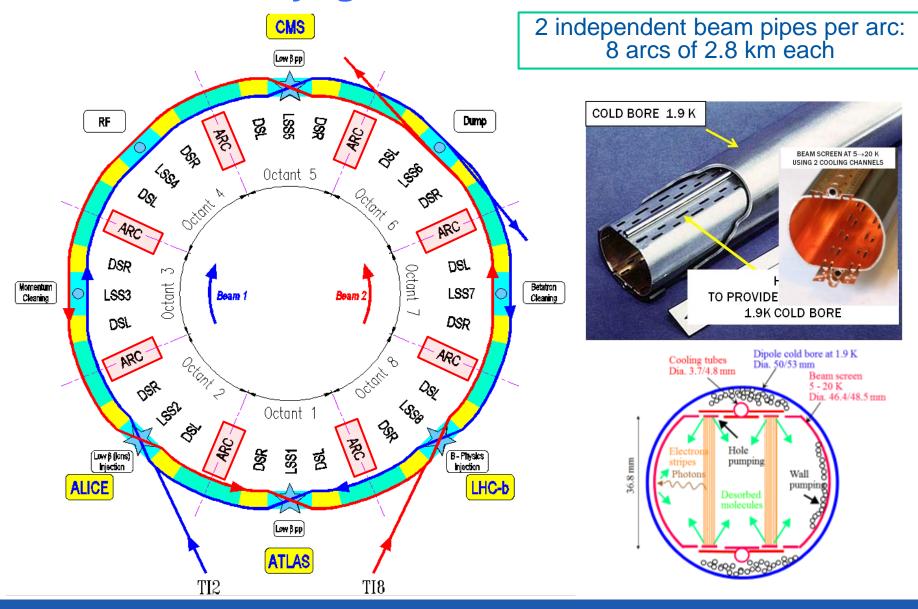




HOPG: highly oriented pyrolitic graphite

3.2 Arc Vacuum System

Cryogenic Beam Vacuum

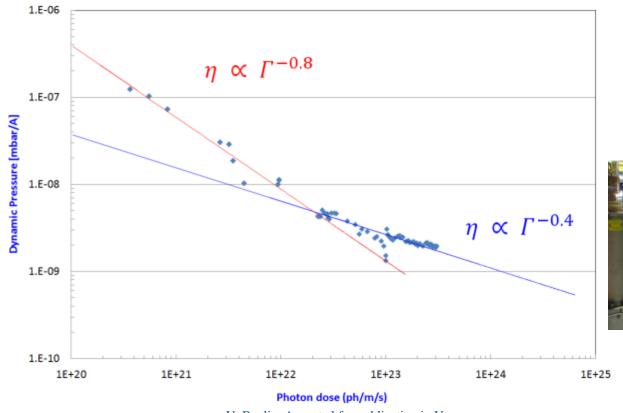




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Beam Conditioning under SR

- Arc extremity's vacuum gauges : unbaked Cu and cryogenic beam screen
- Reduction by 2 orders of magnitude since October 2010



- 2 trends:
- Room temperature
- Cryogenic temperature



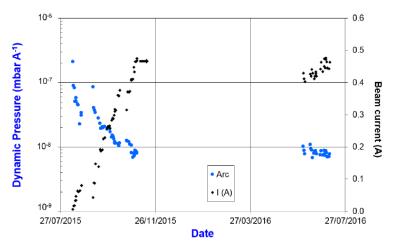
- V. Baglin. Accepted for publication in Vacuum
- Inside the arc, at 5-20 K, deltaP < 10⁻¹⁰ mbar (i.e. below detection limit)
- The photodesorption yield at cryogenic temperature is estimated to be < 10⁻⁴ molecules/photon

Beam Scrubbing

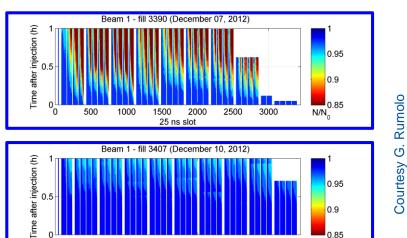
"Scrubbing" periods are required during LHC commissioning. Particularly during bunch spacing

reduction and beam intensity increase

- Increase of beam life time with time
- Strong pressure reduction in a short time
- Heat load reduction with time



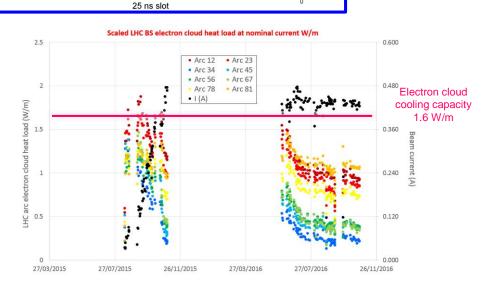
V. Baglin. Accepted for publication in Vacuum



2000

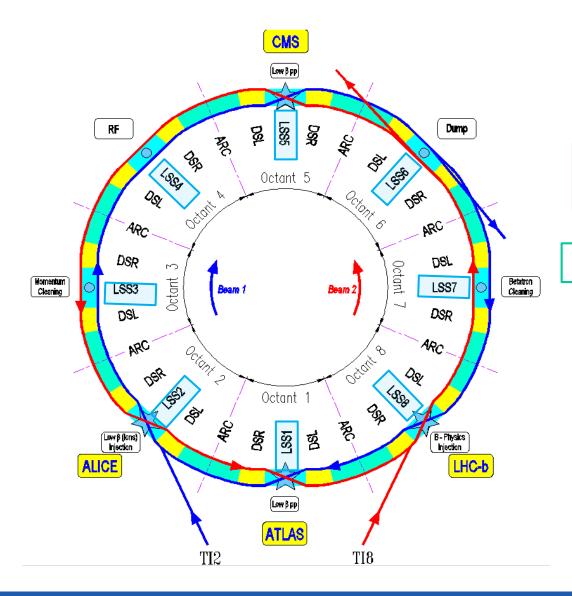
1500

2500



3.3 RT Vacuum System

Room Temperature Beam Vacuum



6 km of RT beam vacuum in the long straight sections

Extensive use of NEG coatings

Pressure <10⁻¹¹ mbar after vacuum activation

Standard Components Installed Inside LSS

• Warm magnets, kickers, septum, collimators, beam instrumentation ...









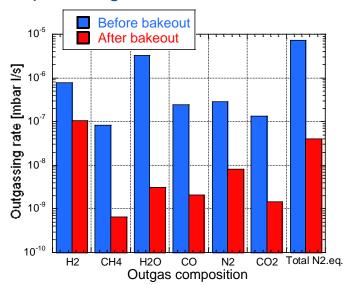
Beam Instrumentations

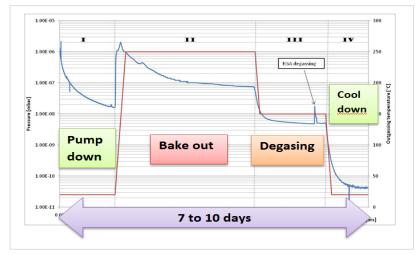


Vacuum Acceptance Tests

 Prior installation more than 2300 LSS's equipments have been baked and validated at the surface :

- leak detection
- residual gas composition
- total outgassing rate
- Example : studies for LHC collimators
 - outgassing rate
 - impact on getter coated vacuum chambers





G. Cattenoz et al. IPAC'14, Dresden 2014

Status	Q (mbar I /s)
Unbaked	7 10 ⁻⁶
1st bake-out	7 10 ⁻⁸
2 nd bake-out	5 10 ⁻⁸
3rd bake-out	4 10-8

J. Kamiya et al. Vacuum 85 (2011) 1178-1181



Room Temperature Vacuum System

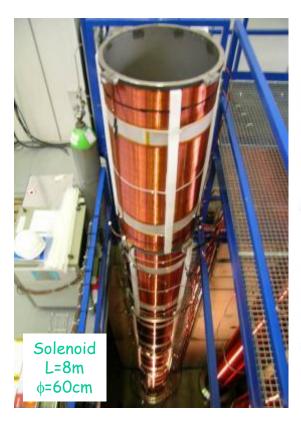
- ~ 1 μm thick, Non Evaporable Getter TiZrV coated vacuum chambers ensure the required vacuum performances for LHC
- Some vacuum chambers were constructed and getter coated ...

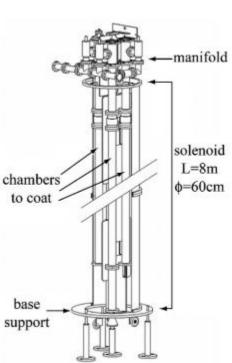


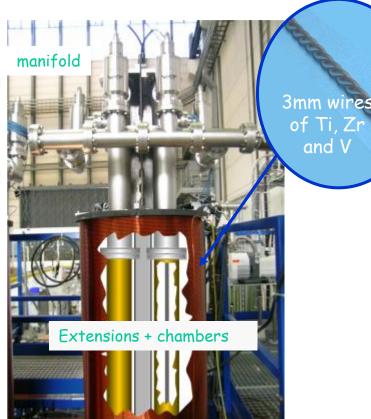
Courtesy R. Veness and P. Chiggiato TE-VSC

LSS Coating System

- Ti-Zr-V is coated by magnetron sputtering with Kr gas
- ~ 1 µm thick
- All room temperature vacuum chamber including the experimental beam pipe are coated with Ti-Zr-V





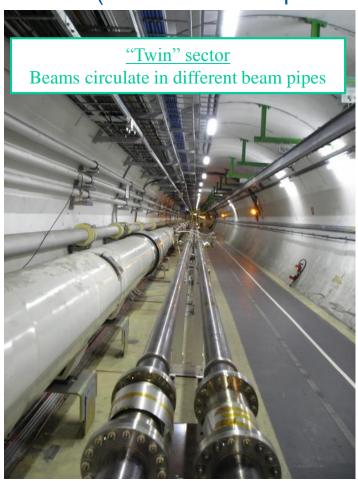


P. Costa Pinto, P. Chiggiato / Thin Solid Films 515 (2006) 382-388



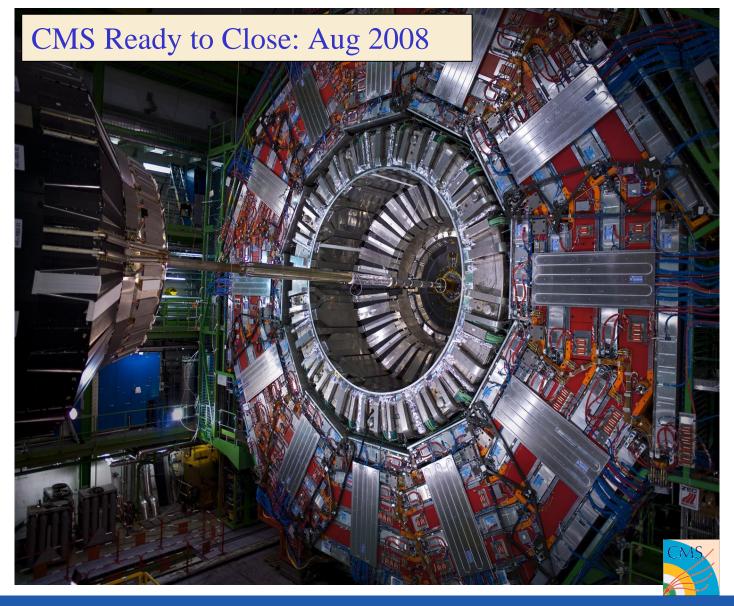
Room Temperature Vacuum System

- and installed inside the LHC tunnel
- to bring the separated beams from the arcs into a single beam pipe for the experiments (held at room temperature!)



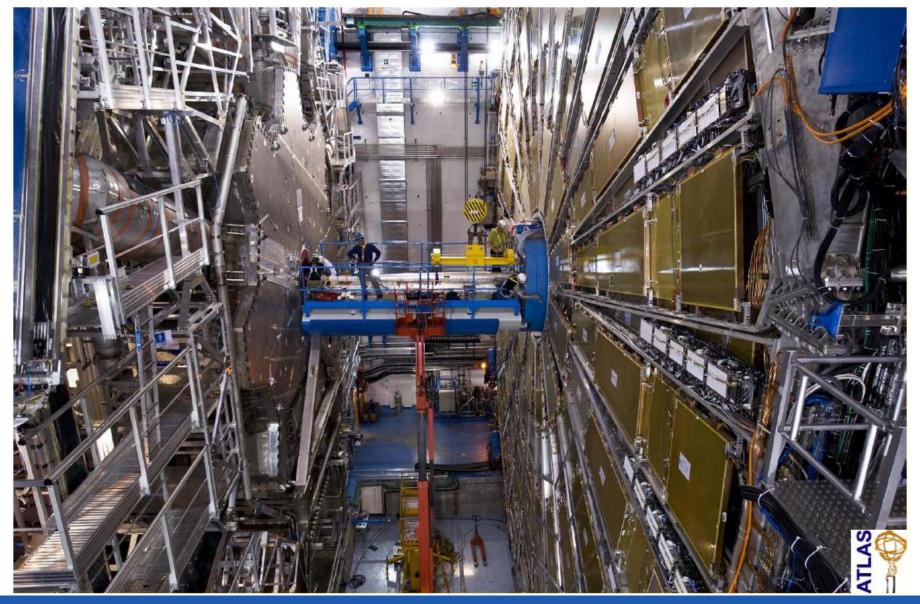


And of Course ... Through the LHC Experiments





Beam Pipe Installation in ATLAS Before Closure

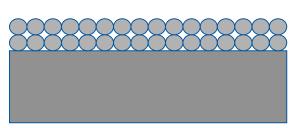




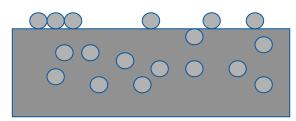
Non-Evaporable Getter (NEG)

Getters are materials capable of chemically adsorbing gas molecules. To do so
their surface must be clean. For Non-Evaporable Getters a clean surface is
obtained by heating to a temperature high enough to dissolve the native oxide
layer into the bulk.

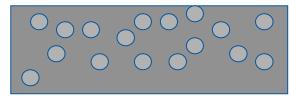
 $T = T_a$ T = RT T = RT



Native oxide layer -> no pumping



Heating in vacuum
Oxide dissolution -> activation



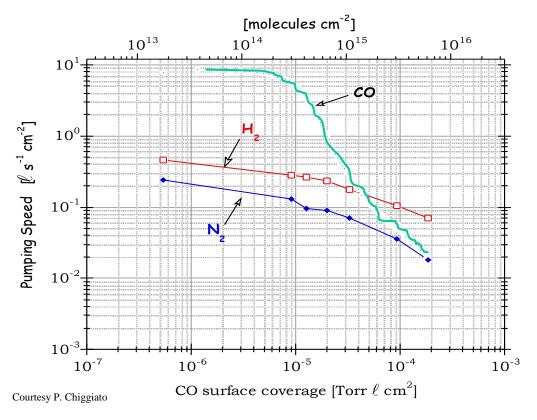
Pumping

NEGs pump most of the gas except rare gases and methane at room temperature

P. Chiggiato and P. Costa Pinto, Thin Solid Films, 515 (2006) 382-388

TiZrV Vacuum Performances

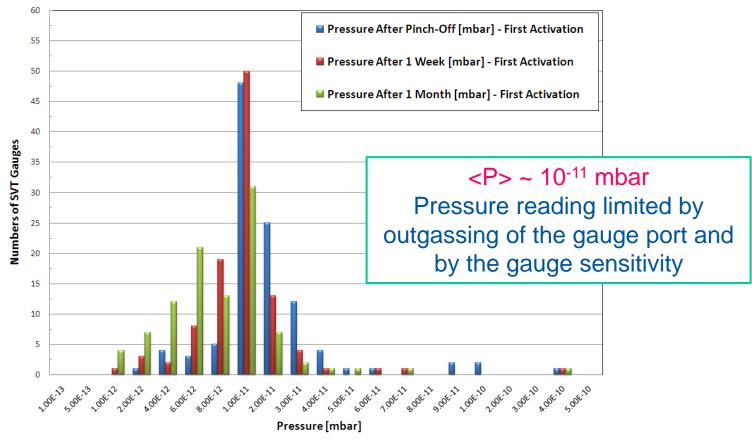
Pumping Speed



- Very large pumping speed : ~ 250 l/s/m for H₂, 20 000 l/s.m for CO
- Very low outgassing rate
- But : limited capacity and fragile coating sensitive to pollutant (hydrocarbons, Fluor ...)

Room Temperature Vacuum System : Static Pressure < 10⁻¹¹ mbar

Ultimate Vacuum Pressure Distribution after NEG Activation of the LHC Room Temperature Vacuum Sectors

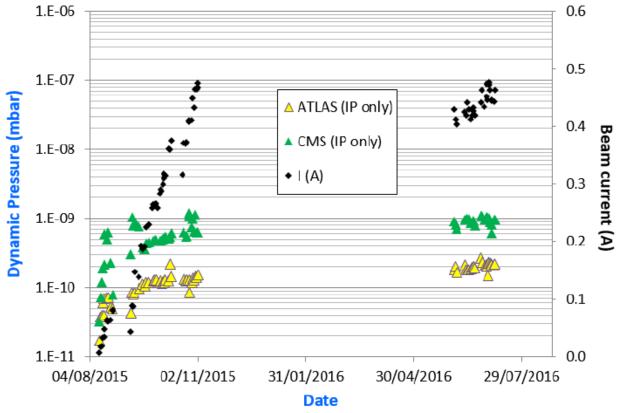


G. Bregliozzi et al. EPAC'08, Genoa 2008



LHC Experimental Areas

- NEG coated vacuum system
 => Large pumping speeds, low SEY and desorption yields
 - <P_{LHC Experiments} > ~ 5 10⁻¹⁰ mbar => with 25 ns bunch spacing and 450 mA => No background issues: within specifications



V. Baglin. Accepted for publication in Vacuum

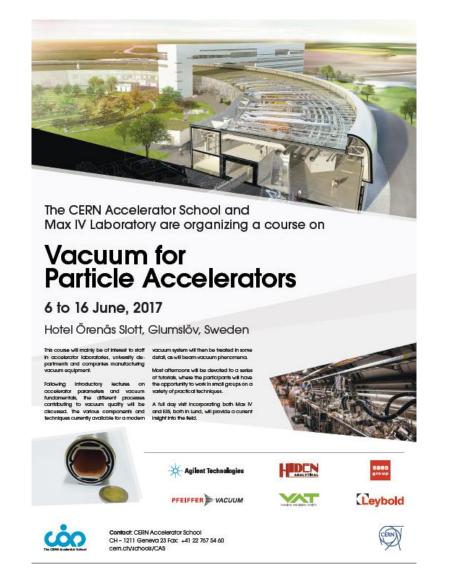


CAS School on Vacuum for Particle Accelerators

6 to 16 June 2017



Hotel Orenas Slott, Glumslov, Sweden



http://cas.web.cern.ch/cas/Lund2017/Lund-advert.html

Programme

DRAFT PROGRAMME FOR VACUUM FOR PARTICLE ACCELERATORS 6-16 June, 2017, Lund, Sweden

- 30 lectures:
 - Overview of the field
- 5 tutorials:
 - Residual gas analysis
 - Leak detection, pumping
 - Computation
 - Mechanical eng.
 - Impedance for vac. sys.
- 2 Visits & 2 seminars:
 - MAX IV the 4th Generation SR source.
 - European Spallation Source (ESS).
- Industrial exhibition
- 1 Excursion

Time	Tuesday	Wednesday	Thursday	Friday	Saturday	Sunday	Monday	Tuesday	Wednesday	Thursday	Friday
	6 June	7 June	8 June	9 June	10 June	11 June	12 June	13 June	14 June	15 June	16 June
08:30		Opening Talks	Materials &	Getter Pumps	Vacuum for		Surface	Transport to	Controlling	Vacuum Design	
			Properties IV:		Thermal		Characterisation	Max IV Lab	Particles/Dust in	Aspects	
			Outgassing		Insulation of				Vacuum Systems		
					Cryogenic						
	A				Equipment						D
09:20	_ ^		P. Chiggiato	E. Maccallini	P. Cruikshank		R. Valizadeh		L. Lilie	H. Reich-Sprenger	"
09:30	R	Introduction to	Vacuum	Ion Pump	Vacuum	1	Interactions	Seminar	Beam Induced	Manufacturing &	E
		Machine	Gauges I	Technology	Gauges II		between Beams	Max IV	Radioactivity &	Assembly for	
	R	Parameters		for Particle			and Vacuum	Laboratory	Radiation Hardness	Vacuum	P
	1			Accelerators		E	System Walls			Technology	A
10:20	٠ .	P. Tavares	K. Jousten	M. Audi	K. Jousten	-	R. Cimino	M. Grabski	F. Cerutti	S. Mathot	A
10.20	v	COFFEE	COFFEE	COFFEE	COFFEE	x	COFFEE	COFFEE	COFFEE	COFFEE	R
11:00	1	Fundamentals of	Mechanical	Introduction	Beam Induced	1	Surface Cleaning	Seminar	Radiation Damage	The Real Life of	1
	A	Vacuum	Vacuum Pumps	to Cryogenics	Desorption	С	& Finishing	ESS	and its Consequence	Operation	T
		Technology						Spallation			
	L					U		Source			U
11:50						R		Vacuum			R
								System			
						S		M. Juni			E
	D	E. Al Dmour	H. Barfuss	S. Claudet	O. Malyshev		M. Taborelli	Ferreira	M. Brugger	V. Baglin	
12:00]	Impedance &	Computation	Cryo-	Beam-Gas	I	Thin-Film	Lunch	Control &	Challenges for	1
	A	Instabilities	for Vacuum	pumping	Interaction	0	Coating		Diagnostic	Vacuum	D
	Y		System of Accelerators			0				Technology of Future Accelerators	L D
	_		Accelerators			N				Future Accelerators	A
13:00		R. Wanzenberg	R. Kersevan	V. Baglin	M. Ferro Luzzi		P. Costa Pinto		P. Gomes	J. Jimenez	
	1	LUNCH	LUNCH	LUNCH	LUNCH]	LUNCH		LUNCH	LUNCH	Y
14:30		Materials &	Tutorial	Tutorial	Tutorial]	Tutorial	1	Tutorial		1
		Properties I:									
		Introduction						Visit to M ax IV		Tutorial	
								10		Work	
15:20	-	S. Sgobba						15:00			
15:30		Materials & Properties II:	Tutorial	Tutorial	Tutorial		Tutorial	15:00	Tutorial	Closeout	
		Thermal &								Closeout	
		Electrical						Visit to ESS			
		Characteristics									
16:20	1	S. Calatroni						4			4
17:00	-	TEA	TEA	TEA Tutorial	TEA Tutorial Work	-	TEA Tutorial	-	TEA Tutorial Work	TEA	4
17:00		Materials & Properties III:	Tutorial Work	Tutorial Work	rutonai Work		Tutorial Work		Tutorial Work	Closing Remarks	
		Mechanical	WOIL	WOLE			WOLL				
		Behaviour									
								1			
17:50		C. Garion				ļ		<u> </u>			1
19:30	Buffet	Dinner	Dinner	Dinner	Dinner	Dinner	Dinner	Dinner	Dinner	Special Dinner	

Some References

- Cern Accelerator School, Vacuum technology, CERN 99-05
- Cern Accelerator School, Vacuum in accelerators, CERN 2007-03
- The physical basis of ultra-high vacuum, P.A. Redhead, J.P. Hobson, E.V. Kornelsen. AVS.
- Scientific foundations of vacuum technique, S. Dushman, J.M Lafferty. J. Wiley & sons.
 Elsevier Science.
- Les calculs de la technique du vide, J. Delafosse, G. Mongodin, G.A. Boutry. Le vide.
- Vacuum Technology, A. Roth. Elsevier Science

Some Journals Related to Vacuum Technolgy

- Journal of vacuum science and technology
- Vacuum

Thank you for your attention !!!

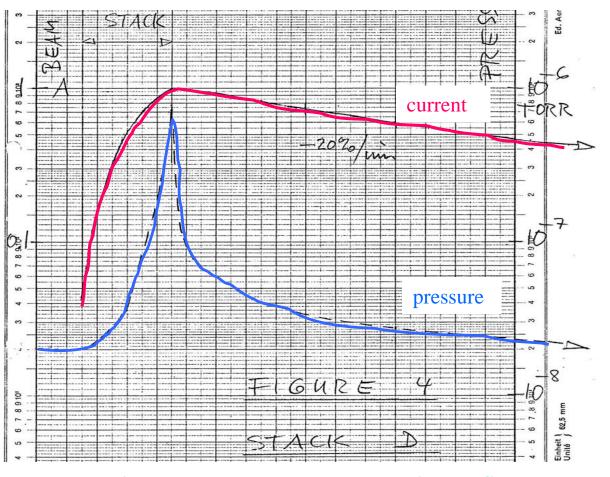


Spare slides

Vacuum Instability: the Effect

• In circular machine with large proton current : ISR, LHC

- Beam current stacking to 1 A
- Pressure increases to 10⁻⁶ Torr (x 50 in a minute)
- Beam losses



First documented pressure bump in the ISR

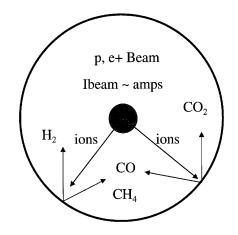
E. Fischer/O. Gröbner/E. Jones 18/11/1970



Vacuum Instability: Mechanism and Recipe

- Origin is ions produced by beam ionisation
- Reduction of the effective pumping speed, S_{eff}

$$P_{eq} = \frac{Q}{S_{eff}} = \frac{Q}{S\left(1 - \frac{\eta_{ion}}{S}\sigma\frac{I}{e}\right)}$$

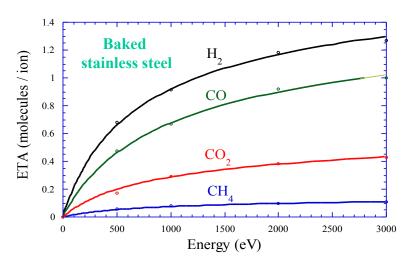


• When the beam current approach the **critical current**, the pressure increases to infinity

$$\left(\eta_{\text{ion}} I\right)_{\text{crit}} = \frac{e S_{\text{eff}}}{\sigma}$$

Recipe:

Reduce η_{ion} Increase pumping speed



A.G. Mathewson, CERN ISR-VA/76-5

LHC Beam Screen Stability

• A minimum pumping speed is provided thanks to the beam screen's holes

$$(\eta_i I)_{\text{crit}} = \frac{e}{\sigma} S_{\text{eff}}$$

	H ₂	CH ₄	CO	CO ₂
$(\eta I)_{crit}$ [A]	1300	80	70	35



Courtesy N. Kos CERN TE/VSC

Beam screen's holes provide room for LHC upgrades

• NB: In the long straight sections, vacuum stability is provided by TiZrV films and ion pumps which are less than 28 m apart

TiZrV Vacuum Performances

- Very low stimulated desorption yield
- SEY ~ 1.1 => very low multipacting
- But: limited capacity and fragile coating sensitive to pollutant (hydrocarbons, Fluor ...)

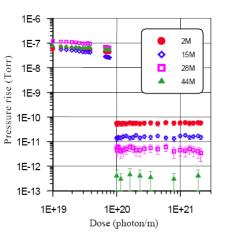


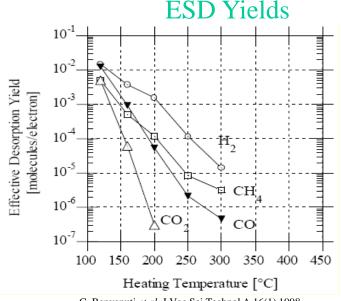
Figure 2: Pressure rise measured in the centre of the TiZrV coated test chamber before activation (<1.10²⁰ photons/m) and after activation (>1·10²⁰ photons/m).

PSD Yields

Table 2: Summary of results from the activated test chamber

Gas	Sticking probability	Photodesorption yield (molecules/photon)
H ₂	~0.007	~1.5·10 ⁻⁵
CH ₄	0	2·10 ⁻⁷
CO (28)	0.5	<1.10-5
C _x H _y (28)	0	<3·10 ⁻⁸
CO ₂	0.5	<2·10 ⁻⁶

V. Anashin et al. EPAC 2002



C. Benvenuti et al. J.Vac.Sci.Technol A 16(1) 1998

Secondary Electron Yield

